

FORM PTO-1449

U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICEATTY. DOCKET NO.
SEPP11.001AUSAPPLICATION NO.
09/836,674INFORMATION DISCLOSURE STATEMENT
BY APPLICANT

(USE SEVERAL SHEETS IF NECESSARY)

APPLICANT
Sven LindforsFILING DATE
April 16, 2001GROUP
1763

U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (IF APPROPRIATE)
MS	US 2001/0000866 A1	5/10/01	Sneh et al.	—	—	

FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO

EXAMINER
INITIAL

OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)

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EXAMINER

Matt Sy Matthew Song

DATE CONSIDERED

7/16/02

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EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (IF APPROPRIATE)
MS	1	6,015,590	1/18/00	Suntola et al.	—	—	
MS	2	5,855,680	1/5/99	Soininen et al.	—	—	
MS	3	4,389,973	6/28/93	Suntola et al.	—	—	
MS	4	4,058,430	11/15/77	Suntola et al.			

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							YES	NO

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OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)

—	5	Handbook of Crystal Growth 3, Thin Films and Epitaxy, Part B: Growth Mechanisms and Dynamics, Page 626.
MS	6	Niinisto et al., "ALD precursor chemistry: evolution and future challenges," Journal de Physique IV. Vol. 9 (1999), pages Pr8-837-Pr8-852.
MS	7	M. Leskela et al., "Synthesis of oxide thin films and overlayers by atomic layer epitaxy for advanced applications," Materials Science & Engineering, Vol. B41 (1996), pages 23-29.
MS	8	Tuomo Suntola, "Atomic layer epitaxy," Thin Solid Films, Vol 216 (1992), pages 84-89

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